

Atty Docket No.: 2000-0484B/N1085-90119

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Patent Application of:	:	
Cheng et al.	:	Group Art Unit: 1765
	:	
Application No.: 10/649,472	:	Examiner: Chen, Kin Chan
	:	
Filing Date: August 27, 2003	:	
	:	
For: Novel Chemical-Mechanical Polishing	:	Date: January 9, 2006
CMP Process for Shallow Trench Isolation	:	
.....	:	

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Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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AMENDMENT AFTER FINAL

Sir:

This paper is responsive to the Office Action dated September 13, 2005. A petition for a one (1) month extension of time to extend the response due date to January 13, 2005 is included herewith. Kindly enter the following amendments:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks begin on page 6 of this paper.